

Inventor: Neal R. Rueger et al.

Title: Methods of Filling Gaps and Methods of Depositing Materials Using High Density Plasma Chemical Vapor Deposition

Assignee: Micron Technology, Inc.

**INFORMATION DISCLOSURE STATEMENT**

References – See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No admission is made regarding whether any of the submitted references is prior art. Copies of any foreign patent documents and non-patent literature are attached.

Respectfully submitted,

Dated:

*September 23, 2003*

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2145		SERIAL NO. Not yet assigned	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Neal R. Rueger et al.		GROUP Not yet assigned	
				FILING DATE Filed herewith			
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	6,331,494 B1	12-2001	Olson et al.			
	AB	6,395,150 B1	05-2002	Van Cleemput et al.			
	AC	6,077,791	06-2000	DeTar			
	AD	5,872,058	02-1999	Van Cleemput et al.			
	AE	6,030,881	02-2000	Papasouliotis et al.			
	AF	5,972,765	10-1999	Clark et al.			
	AG	6,025,280	02-2000	Brady et al.			
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes    No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR						
	AS						
	AT						
EXAMINER				DATE CONSIDERED			
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>							